STATES PATENT AND TRADEMARK OF E PATENT APPLICATION 2812 Group Art Unit S. MULPURI MANABE et al. Examiner: Inventor(s): Atty. Dkt. 273686 F00-219-USdiv3 677,781 Appln. No.: 09 Series Code ↑ M# Client Ref A METHOD FOR MANUFACTURING A Appln. Title: Filed: October 2, 2000 GALLIUM NITRIDE GROUP Hon. Commissioner of Patents COMPOUND SEMICONDUCTOR JUL 1 2 2002 Washington, D.C. 20231 Sir: REPLY/AMENDMENT/LE July 12, 2002 This is a reply/amendment/letter in the above-identified application and includes the herewith attachment of same date and subwhich is incorporated hereinto by reference and the signature below is treated as the signature to the attachment in absence of a signature thereto. FEE REQUIREMENTS FOR CLAIMS AS AMENDED 1. Small Entity claim For B & C Fee Code Highest number Present Extra Large/Small Entity Additional A. MOT made Claims See Required remaining after previously paid for Fee B. Withdrawn Separate Paper C. made herewith amendment Lg/Sm (Pat-256) D. made previously 2. Total Effective Claims 64 **minus 100 x \$18/\$9 =+ \$0 103/203 102/202 x \$84/\$42 =+ \$0 4 ***minus 6 0 3. Independent Claims 4. If amendment enters proper multiple dependent claim(s) into this application for first + \$0 + \$280/\$140 = 104/204 ☐ NONE 5. Original due Date: May 12, 2002 115/215 6. Petition is hereby made to extend the original due (1 mo) \$110/\$55 = 116/216 + \$400 date to cover the date this response is filed for which the (2 mos) \$400/\$200 = 117/217 (3 mos) \$920/\$460 = requisite fee is attached 118/218 (4 mos) \$1,440/\$720= 128/228 (5 mos) \$1,960/\$980= - \$0 7. Enter any previous extension fee paid since above original due date and subtract + \$400 **Extension Fee** + \$110/\$55 + \$0 148/248 9. If Terminal Disclaimer attached, add Rule 20(d) official fee 126 10. If IDS attached requires Official Fee under Rule 97 (c), add + \$180 + \$0 126 + \$180 or if Rule 97(d) Requestadd 146/246 11. After-Final Request Fee per rules 129(a) and 17(r) + \$740/370 + \$0 149/249 12. No. of additional inventions for examination per Rule 129(b)..... x \$740/370 ea + \$0 1179/1279 13. Request for Continued Examination (RCE) + \$740/370 + \$0 + \$0 14. Petition fee for **TOTAL FEE =** \$400 15. 16. *If the entry in this space is less than entry in next space, the "Present Extra" result is "0". PLEASE CHARGE 17. **If the "Highest number previously paid for" in this space is less than 20, write "20" in this space. OUR DEP. ACCT 18, ***If the "Highest number previously paid for" in this space is less than 3, write "3" in this space. Our Deposit Account No. 03-3975) (Our Order No. 31317 273686

CHARGE STATEMENT: The Commissioner is hereby authorized to charge any fee specifically authorized hereafter, or any missing or insufficient fee(s) filed, or asserted to be filed, or which should have been filed herewith or concerning any paper filed hereafter, and which may be required under Rules 16-18 (missing or insufficiencies only) now or hereafter relative to this application and the resulting Official Document under Rule 20, or credit any overpayment, to our Accounting/Order Nos. shown above, for which purpose a duplicate copy of this sheet is attached.

This CHARGE STATEMENT does not authorize charge of the issue fee until/unless an issue fee transmittal sheet is filed.

Sig:

Query: Is appeal deadline now? If so, file Notice of Appeals separately

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NOTE: File this cover sheet in duplicate with PTO receipt (PAT-103A) and attachments



IN THE UNITED STATES PATENT AND ...

In re PATENT APPLICATION OF Confirmation No.: 4206

MANABE et al. Group Art Unit: 2812

Appln. No.: 09/677,781 Examiner: S. MULPURI

Filed: October 2, 2000

Title: A METHOD FOR MANUFACTURING A GALLIUM NITRIDE GROUP COMPOUND

CEMICONDUCTOR

July 12, 2002

12/C

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Hon. Commissioner of Patents Washington, D.C. 20231

Sir:

In response to the Office Action dated February 12, 2002, please amend the application identified above as follows:

IN THE CLAIMS:

Please cancel claims 111 and 112 without prejudice or disclaimer.

Please enter the following amended claims 53-56:

53. A method for producing a gallium nitride group compound (Amended) semiconductor by an organometallic compound vapor phase epitaxy, comprising the steps of:

setting a supplying rate of silicon (Si) to gallium (Ga) in a reaction chamber during said vapor phase epitaxy at a desired value in a range from 0.1 to 3 as converted values so as to control conductivity (1/resistivity) of said gallium nitride group compound semiconductor at a desired value such that said conductivity increases with increasing of said supplying ratio, where said values 0.1 and 3 are the values obtained from gas flow rates, in case that an amount of said gallium (Ga) is converted into a flow rate of hydrogen bubbling trimethyl gallium (TMG) at a temperature of -15°C and an amount of said silicon (Si) is converted into a flow rate of a gas diluted to 0.86 ppm.

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A method for producing a gallium nitride group compound (Amended) semiconductor by an organometallic compound vapor phase epitaxy, comprising the steps of: